DECLARATION

As a below named inventor, I/we hereby declare that:

My residence, post office address and citizenship are as stated below next to my name; that

I/we verily believe I am the original and first inventor(s) of the invention entitled: ATOMIC LAYER DEPOSITION WITH POINT OF USE GENERATED REACTIVE GAS SPECIES, described and claimed

X	in the attached specification;	
	in the specification filed	, as U.S. Application Serial No.
	, and as amended	·

I/we hereby authorize the attorney(s) and/or agent(s) appointed herein to indicate above whether the invention is described and claimed in an attached specification and to provide the Filing Date and Serial No. of the corresponding U.S. Application, if previously filed.

I/we hereby state that I/we have reviewed and understand the contents of the above identified specification, including the claims as filed and as amended by any amendment referred to above.

I/we acknowledge the duty to disclose to the Patent and Trademark Office all information known to me to be material to patentability as defined in Title 37, Code of Federal Regulations, §1.56(a).

I/we further declare that all statements made herein of my/our own knowledge are true and that all statements made on information and belief are believed to be true; and further that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under §1001 of Title 18 of the United States Code, and that such willful false statements may jeopardize the validity of the application or any patent issuing thereon.

Full name of sole or first Inventor: Gurtej S. Sandhu

Inventor's signature

Date: 2/21/62

Residence:

2964 E. Parkriver Drive

Boise, Idaho 83706

Citizenship: UK

Post Office Address: c/o Micron Technology, Inc.

8000 S. Federal Way Boise, ID 83706-9632